

10th International Conference of the European Society for Precision Engineering and Nanotechnology

Session 1: Emerging Patterning Technologies and Methods

Tuesday 1st June 2010, 10:00-11:00

Chairmen: Prof J. Van Eijk, University of Delft, NL & Dr J. Benschop, ASML, NL

O1.1 (Keynote)	Nanoimprint Lithography S.V. Sreenivasan <i>Molecular Imprints, US</i>
O1.2	Novel FIB-SEM Based Methods for Nano-Patterning and Nano-Prototyping Dr Pybe Faber <i>FEI, NL</i>
O1.3	A High Precision System for Aligned Metal Printing on Wafers Using ECPR - ElectroChemical Pattern Replication Patrick Möller <i>Replisaurus Technologies, SE</i>